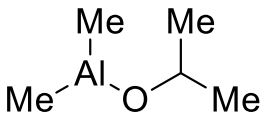
Catalog # D281774 Dimethylaluminum i-propoxide, 98% (99.99+%-Al) PURATREM



Technical Notes

Used as MOCVD precursor for making of $CoAl_2O_4$ films [1], ALD precursor for making of Al_2O_3 films [2-6, 8-10], and as a Al doping source for ZnO films [7].

References:

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6. *J. Vac. Sci. Technol. A,* **2014**, *32,* 021514
7. *J. Mater. Chem. C,* **2015**,*3,* 3095
8. *Thin Solid Films,* **2017**, *641,* 47